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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANTS: Ja-Hum KU et al. CONF. NO.: 4261
SERIAL NO.: 10/612,041 GROUP: 2829
FILED: July 3, 2003 EXAMINER: Kilday, Lisa A.

FOR: A METHOD OF FABRICATING A SEMICONDUCTOR DEVICE
HAVING A SILICON OXIDE LAYER, A METHOD OF FABRICATING A
SEMICONDUCTOR DEVICE HAVING DUAL SPACERS, A METHOD OF
FORMING A SILICON OXIDE LAYER ON A SUBSTRATE, AND A
METHOD OF FORMING DUAL SPACERS ON A CONDUCTIVE
MATERIAL LAYER

DOCKET NO.: 2557-000153/US

RESPONSE TO ELECTION OF SPECIES REQUIREMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

July 30, 2004

Dear Sir:

In response to the Examiner's Election of Species Requirement dated June 30, 2004, the following election and remarks are respectfully submitted in connection with the above-referenced application.